

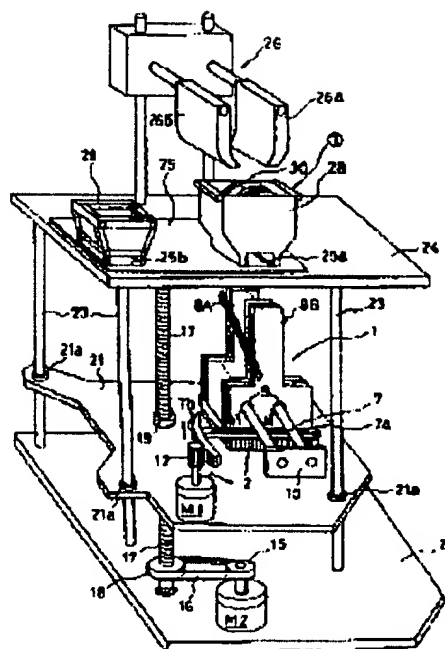
**SHIFTER FOR SEMICONDUCTOR WAFER**

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**Abstract of JP1048442**

**PURPOSE:**To treat semiconductor wafers under ideal conditions, and to improve quality by providing a space changing means changing the spaces of a plurality of semiconductor wafers at the time of proceeding and the time of returning to a holding means of a semiconductor-wafer support means.

**CONSTITUTION:**When a plurality of semiconductor wafers are shifted between a first base section (a 'Teflon(R)' carrier) 28 and a second base section (a quartz carrier) 29, a lever 7 is turned, and the spaces of the wafers 30 are altered by a pitch changer 2 at the time of lifting and the time of lowering of a wafer supporter 1. Consequently, a large number of the wafers 30 are varied to desired spaces at a stroke and can be shifted between the 'Teflon (R)' carrier 28 and the quartz carrier 29. Accordingly, the wafers 30 can be treated at spaces proper for CVD treatment, thus improving the quality of the wafers 30, then quickly shifting the wafers.



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